

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1. (Previously Presented) A fabricating method of a plasma display panel, comprising:

providing a sheet into which a black material layer and an electrode material layer are integrated;

forming the sheet on a substrate;

aligning a first mask on the front surface of a substrate where the sheet has been formed and exposing the sheet;

aligning a second mask on the rear surface of the substrate and exposing the sheet;

and

developing the exposed sheet to form a bus electrode and a light shielding layer.

2. (Previously Presented) The fabricating method according to claim 1, wherein developing the exposed sheet includes:

developing the black material layer and the electrode material layer at the same time.

3. (Original) The fabricating method according to claim 2, wherein the exposure using the first mask is made by use of an ultraviolet ray of around  $200\sim 800\text{mJ}/\text{cm}^2$ .

4. (Original) The fabricating method according to claim 2, wherein the exposure using the second mask is made by use of an ultraviolet ray of around  $400\sim 1000\text{mJ}/\text{cm}^2$ .

5. (Original) The fabricating method according to claim 1, wherein the bus electrode is formed of the black material layer and the electrode material layer.

6. (Previously Presented) The fabricating method according to claim 5, wherein the black material layer includes ruthenium Ru and Cobalt Co of  $50\sim 60\%$ , solvent of  $20\sim 30\%$  and photosensitive resin of  $25\sim 35\%$ .

7. (Original) The fabricating method according to claim 5, wherein the electrode material layer includes silver Ag of  $50\sim 60\%$ , solvent of  $20\sim 30\%$  and photosensitive resin of  $25\sim 35\%$ .

8. (Currently Amended) The fabricating method according to claim 1, further comprising:

forming a dielectric body on the substrate on which the bus electrode and a black matrix-the light shielding layer have been formed; and

forming a protective film on the substrate on which the dielectric body has been formed.

9. (Previously Presented) The fabricating method according to claim 1, wherein providing the sheet includes:

joining the black material layer with the electrode material layer in a laminating process.

10. (Previously Presented) The fabricating method according to claim 1, wherein forming the sheet on the substrate includes:

joining the substrate with the sheet in a laminating process.

11. (Previously Presented) A fabricating method of a plasma display panel, comprising:

providing a sheet into which a black material layer and an electrode material layer are integrated;

forming the sheet on a substrate;

aligning a first mask and a second mask on the front surface and the rear surface of a substrate where the sheet has been formed, respectively; and

exposing the sheet by use of the first and second masks and developing the sheet to form a bus electrode and a light shielding layer.

12. (Previously Presented) The fabricating method according to claim 11, wherein forming the bus electrode and the light shielding layer includes:

exposing the electrode material layer and the black material layer of the sheet by use of the first mask, and at the same time exposing the black material layer of the sheet by use of the second mask; and

developing the black material layer and the electrode material layer of the exposed sheet simultaneously.

13. (Previously Presented) The fabrication method according to claim 1, wherein the light shielding layer is formed from a portion of the black material layer.

14. (Currently Amended) The fabrication method according to claim 2, wherein the ~~black matrix~~ light shielding layer is formed from the black material layer.

15. (Currently Amended) A plasma display panel fabricating method, comprising:  
attaching a prefabricated layer to a substrate, wherein the prefabricated layer  
comprises a black material layer and an electrode layer;  
aligning a first mask on a front surface of a substrate, and aligning a second mask  
on a rear surface of the substrate;  
exposing the prefabricated layer using the first and second masks;  
developing the prefabricated layer;  
forming at least one electrode using the black material and electrode layers of the  
prefabricated layer, wherein the electrode is formed by exposing the prefabricated layer through  
the first mask on the front surface of the substrate; and  
forming at least one black matrix using the black material of the prefabricated  
layer, wherein the black matrix is formed by exposing the prefabricated layer through the second  
mask on the rear surface of the substrate.

16-17. (Canceled).

18. (Previously Presented) The method of claim 15, wherein the black material layer  
includes ruthenium Ru and cobalt Co of 50~60%, solvent of 20~30% and photosensitive resin  
of 25~35%.

19. (Previously Presented) The method of claim 15, wherein the electrode layer includes silver Ag of 50~60%, solvent of 20~30% and photosensitive resin of 25~35%.

20. (Currently Amended) The method of claim 15, wherein the prefabricated layer is attached to the substrate with ~~at least one of a~~ temperature around 50 ~ 80°C and pressure around 1.5Kg/cm<sup>2</sup>.

21. (Previously Presented) The method of claim 15, wherein the prefabricated layer is formed by laminating the black material layer and the electrode layer.

22. (Currently Amended) The method of claim 21, wherein the lamination occurs in ~~at least one of~~ temperature around 70 ~ 90°C and pressure around 3 ~ 4 Kg/cm<sup>2</sup>.

23. (Canceled).